

SiC Power Devices

vol.3



The Industry's First Mass-Produced "Full SiC" Power Modules

ROHM now offers SiC power devices featuring a number of characteristics, including: high breakdown voltage, low power consumption, In response to the growing demand for SiC products, ROHM has implemented the world's first full-scale, mass production of next-generation SiC components.



- and high-speed switching operation not provided by conventional silicon devices.

SiC - the next generation of compact, energy-saving Eco Devices

The demand for power is increasing on a global scale every year while fossil fuels continue to be depleted and global warming is growing at an alarming rate. This requires better solutions and more effective use of power and resources. ROHM provides Eco Devices designed for lower power consumption and high efficiency operation. These include highly integrated circuits utilizing sophisticated, low power ICs, passive components, opto electronics and modules that save energy and reduce CO₂ emissions. Included are next-generation SiC devices that promise even lower power consumption and higher efficiency.

Lower power loss and high temperature operation in a smaller form factor

In the power device field for power conversion and control, SiC (Silicon Carbide) is garnering increased attention as a next-generation semiconductor material due to its superior characteristics compared with silicon, including lower ON-resistance, faster switching speeds, and higher temperature operation.

Implementing SiC devices in a variety of fields, including the power, automotive, railway, industrial, and consumer sectors

SiC devices allow for smaller products with lower power consumption that make mounting possible even in tight spaces. Additional advantages include high voltage and high temperature operation, enabling stable operation under harsh conditions-impossible with silicon-based products. In hybrid vehicles and EVs SiC power solutions contribute to increased fuel economy and a larger cabin area, while in solar power generation applications they improve power loss by approximately 50%, contributing to reduced global warming.



700 € 600 € 500 · 400 -300 -200 -0.

Industrial equipment Reduces power loss and size



Consumer electronics Energy-saving air conditioners and IH cooktops Servers Reduce data center power consumption by minimizing server power loss



EV (i.e. hybrid/electric vehicles) Reduce cooling system size, decrease weight. and increase fuel economy

conditioner efficiency

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Power Loss Comparison

Power Loss per Arm

(W)

300

0



■long - term market forecast for SiC devices in various power applications



Market forecast for SiC power devices Source: Yole Développement

Railway

Power transmission systems Reduce power loss

Reduce inverter size and weight

The industry's first mass-produced SiC makes the previously impossible "possible"

SiC Power Device

Full SiC Power Module

Mass Produced

Switching loss reduced by 85% (max.)

ROHM has developed low-surge-noise power modules integrating SiC devices produced in-house, maximizing high-speed performance. The result is significantly reduced switching loss compared with conventional Si IGBTs.



Features (BSM120D12P2C005)

- 1 Switching loss reduced by 85% (max.)*
- 2 50% less volume*
- 3 High-speed switching
- 4 1200V rated voltage / 120A rated current *Compared with conventional Si IGBT modules



Reference values evaluated under the same conditions

■ Ideal replacement for Si IGBT modules

ROHM SiC power modules reduce switching loss considerably, making them ideal for replacing Si IGBT modules (depending on the operating conditions).

Si IGBT (200A to 400A)



Full SiC Power Module (120A)





BVDss 1200V ID 120A 180A Module BSM120D12P2C005 Xerry BSM180D12P2C101

SiC MOSFET

Mass Produced

High speed switching with low ON- resistance

SiC enables simultaneous high speed switching with low ON-resistance – normally impossible with silicone-based products. Additional features include superior electric characteristics at high temperatures and significantly lower switching loss, allowing smaller peripheral components to be used.



Internal Circuit Diagram









Lineup

Deelvere	BVDSS 400V	650V	1200V						
Раскаде	RDS (on) 120mΩ	120mΩ	80mΩ	160mΩ	280mΩ	450mΩ			
TO-220AB [3pin]	New SCTMU001F	New SCT2120AF	—	—	—	—			
TO-247			SCH2080KE	New/	New/	New/			
[3pin]	_		SCT2080KE	SCT2160KE	SCT2280KE	SCT2450KE			



ROHM's unique IC technology maximizes SiC characteristics

DRIVER

SiC SBD (Schottky Barrier Diodes)

Mass Produced

Significantly lower switching loss

SBDs were developed utilizing SiC, making them ideal for PFC circuits and inverters. Ultra-small reverse recovery time (impossible to achieve with silicon FRDs) enables high-speed switching. This minimizes reverse recovery charge (Qrr), reducing switching loss considerably and contributes to end-product miniaturization.





Lineup

2nd Generation														
	650V					1200∨								
Раскаде	6A	8A	10A	12A	15A	20A	30A	40A	5A	10A	15A	20A	30A	40A
TO-220AC[2pin]	SCS206AG	SCS208AG	SCS210AG	SCS212AG	New SCS215AG	SCS220AG	_	_	SCS205KG	SCS210KG	SCS215KG	SCS220KG	—	—
TO-220FM[2pin]	SCS206AM	SCS208AM	SCS210AM	SCS212AM	New SCS215AM	New SCS220AM	—	_	—	—	—	—	—	_
TO-247[3pin]	—	_	_	—	—	SCS220AE2	New SCS230AE2	SCS240AE2	_	SCS210KE2	—	SCS220KE2	New SCS230KE2	New SCS240KE2
LPTL[4pin]	New SCS206AJ	New SCS208AJ	New SCS210AJ	New SCS212AJ	New SCS215AJ	New SCS220AJ	_	_	_			_	_	_

Isolated Gate Driver

Under Development

High-speed operation supports SiC

•High-speed operation with a max. I/O delay time of 150ns •Core-less transformer utilized for 2,500Vrms isolation ·Original noise cancelling technology results in high CMR (Common Mode Rejection).

 Supporting high VGS/negative voltage power supplies*
 BM6101FV-C,
 BM6104FV-C •Compact package (6.5×8.1×2.01 mm)

Recommended Operating Range (BM6101FV-C)

Parameter	Symbol	Min.	Max.	Unit
Input Supply Voltage	VCC1	4.5	5.5	V
Output Supply Voltage	VCC2	14	24	V
Output VEE Voltage	VEE2	-12	0	V
Operating Temperature Range	Та	-40	125	C

■ IPM Operating Waveforms (BM6101FV-C)



Lineup

	Features									
Part No.	Rated Output Current (Peak)	Isolation Voltage	Negative Power Supply Compatibility	I/O Delay Time	Over current Detection	DESAT	Mirror Clamp Function	Soft Turn OFF Function	Error Status Output	
BM6101FV-C	3.0A	2,500Vrms	0	350ns	0	0	0	0	0	
BM6102FV-C	3.0A	2,500Vrms	—	200ns	0	0	0	0	0	
BM6104FV-C	3.0A	2,500Vrms	0	150ns	0	0	0	0	0	



High quality ensured through a consistent production system

Quality First is ROHM's official corporate policy. In this regard a consistent production system was established for SiC production. The acquisition of SiCrystal (Germany) in 2009 has allowed ROHM to perform the entire manufacturing process, from wafer processing to package manufacturing, in-house. This not only ensures stable production and unmatched quality, but lowers cost competitiveness and enables the development of new products.



ASSYLINE In-house production equipment

High quality, high volume, and stable manufacturing are guaranteed utilizing in-house production equipment

WAFER PROCESS SiC processes

High quality lines integrating SiC's unique processes are utilized.

DISCRETE

Transisto

Low inductance module A low inductance module utilizing SiC's high-speed characteristics

was developed

SiCrystal

SiCrystal AG, the largest SiC monocrystal wafer manufactu became a member of the ROHM Group in 2009.

SiCrystal was established in 1997 in Germany based on a monocrystal growth technology development project laur Mass production and supply of SiC wafers began in 2001. In 2012, SiCrystal relocated to a new plant in Nüremberg With the corporate philosophy "Stable Quality", SiCrystal h an integrated wafer production system from raw SiC mater wafer processing, and inspection, and in 1999 was granted

Manufactured Product: SiC Wafers



SiC Wafer Production

Advanced Crystallization Technology

SiC ingots are produced via a crystal growth process utilizing a sublimation method called "Rayleigh's method" that sublimates SiC powder and recrystallizes it under cold temperatures. Compared with conventional Si ingots which are crystalized in the liquid phase from Si melt, the growth rate using the sublimation method is slow, making crystal defects likely to occur, and therefore requires precision technology for crystal control. SiCrystal utilizes advanced crystallization technology to produce stable quality wafers.



Temperature: 2,000 to 2,400°C Principle: Transports sublimated gas to the surface of the seed crystal by a heat gradient in order to recrystallize it. Crystal control is difficult and the growth rate is slow compared with

Water-Cooled

1. Crystal

growth

liquid phase growth.



2. External polishing

3. Flat formation



CHIP DESIGN High quality design

Master engineers are on hand to ensure high quality designs.



CAD

In-house photo masking

Enabling uniform quality control from SiC chip design to photo masking

ON SITE PLANT

manufacturing facility

Cutting-edge, self-sufficient

In addition to in-house power generation, all materials required for

manufacturing, such as hydrogen,

oxygen, and nitrogen, are included



ROHM acquired SiCrystal (a German SiC substrate manufacturer), resulting in stable supply of high-quality SiC substrates.

NÜR	NBERG
irer in Europe,	
SiC	
iched in 1994	
to increase production capacity. has adopted rial to crystal growth, d ISO9001 certification.	
mm ch)	

Acquired ISO9001 Certification



For Si:

Temperature: 1,230 to 1,260°C Principle: Liquid-phase growth during which Si melt is solidified on the seed crystal. This method is characterized by fast

crystal growth.



4. Slicing



5. Sanding / Edge polishing / Cleaning





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State-of-the-art industry-academia R&D collaboration

ROHM is actively involved in partnerships with major universities in a variety of fields in order to share expertise, cultivate new technologies, and collaborate on breakthrough R&D.

Development of mass-produced SiC epitaxial growth equipment

Kyoto University × Tokyo Electron × ROHM 3-institution technological collaboration enables rapid development of high-quality SiC devices

In 2007 ROHM, along with Kyoto University and Tokyo Electron, developed mass production SiC epitaxial growth equipment that can processes multiple SiC wafers in a single operation. Fast development was made possible by efficiently sharing technologies. These new equipment are currently used for mass producing ROHM SiC devices.

High performance SiC MOSFET with High-k gate is currently under development

Osaka University × Kyoto University × Tokyo Electron × ROHM

Characteristics improvement based on new materials, 1.5 times the breakdown voltage, 90% lower leakage current

Developed the industry's first SiC Trench MOSFET utilizing an aluminum oxynitride (AION) layer on the gate insulating film. The result is 1.5x the breakdown voltage and 90% lower leakage current vs. conventional thermally oxidized films (SiO2) for greater reliability with lower loss. Expected to find wide adoption in electric vehicles, industrial equipment, and trains in the near future.



Development of high temperature operation (Tj=225°C) transfer mold modules

ROHM has developed SiC modules capable of operating at thigh temperatures for inverter driving in automotive systems and industrial devices. These transfer mold modules are the first in the industry to ensure stable operation up to 225°C while maintaining the compact, low-cost package configurations commonly used in current Si devices. This contributes to wide compatibility and ensures ready adoption. Modules incorporating 6 devices and featuring 1200V/300A operation at temperatures up to 225°C are available.

Future solutions for high temperature operation



High temperature SiC gate drivers Gate drivers using SOI wafers are currently under development. They are expected to achieve higher speeds with lower power consumption.

SiC high temperature devices Operation has been verified above 200°C. Evaluating reliability at high temperatures is the next step.





High temperature capacitors Devices featuring new materials and designs are currently being developed with higher temperature capability.



packaging technology Unique technology was used to develop high temperature packaging suitable for SiC devices.

High temperature

Proprietary technology makes it possible to develop ultra-compact large current SiC IPMs.

ROHM, in collaboration with major motor manufacturers, is focused on developing SiC modules for next-generation vehicle motors that utilize a number of compact products developed in-house, from gate driver ICs to transistors, diodes, and resistors. Previously, no electronic devices could be built into motors due to the extreme temperatures. However, ROHM SiC module technology allows compact integration of electronic components within the motor, making it possible to produce high efficiency motors with built-in inverters. An ultra-compact large current SiC IPM has been realized by attaching a high-temperature-resistant micro-mold-type SiC module directly to a cooler.



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High temperature operation, high voltage IPM (Intelligent Power Module) High temperature, high voltage devices manufactured in-house combined with original high heat resistant packaging technology.







Focusing on cutting-edge SiC technology and leading the industry through innovative R&D

ROHM has been focused on developing SiC for use as a material for next-generation power devices for years, collaborating with universities and end-users in order to cultivate technological know-how and expertise. This culminated in Japan's first mass-produced Schottky barrier diodes in April 2010 and the industry's first commercially available SiC transistors (MOSFET) in December. And in March 2012 ROHM unveiled the industry's first mass production of Full SiC Power Modules.

2007

SiC Technology Breakthroughs



2002







Honda R&D Co., Ltd. and ROHM test prototype SiC

power modules for hybrid

ROHM tests prototype high

vehicles 1

(Sep 2008)

History

2002	2003	2007
	Contraction of the second s	
Begin preliminary experiments with SiC MOSFETs (Jun 2002)	Ship SiC MOSFET samples (Nov 2005)	ROHM, along with Kyo University and Tokyo Electro announce the development
Develop SiC MOSFET prototypes	Announce the development of SiC MOSFETs with the	SiC epi film mass-production technology
(Dec 2004)	industry's smallest ON-resistance $(3.1 m\Omega cm^2)$	(Jun 2007)
	(Mar 2006)	Trial manufacture of lar

2005

current (300A) SiC MOSFET and SBDs (Schottky Barrier Diodes) (Dec 2007)

Develop a new type of SiC diode with Nissan Motors (Apr 2008)

2008

Release trench-type MOSFETs eaturing the industry's smallest ON-resistance: 1.7mΩcm² (Sep 2008)

transfer mold SiC power modules

capable of high temperature

operation (up to 225°C) 5

(Oct 2011)

(Oct 2011)

(Sep 2008)

temperature operation power modules that utilize SiC elements Nissan Motors conducts a and introduces a demo capable driving experiment of a fuel-cell of operation at 250 °C 2 vehicle equipped with an (Oct 2008) inverter using ROHM's SiC diode



Launch the industry's first mass production of "Full SiC' power modules with SiC SBDs and SiC MOSFETs 6 (Mar 2012)

Begin mass production of SiC-MOS Module (Dec 2012)



SiC Eco Devices Reducing environmental load

SiC power devices deliver superior energy savings. environmental impact.



A Group acquires an SiC wafer acturer 3

Develop the industry's first high current low resistance SiC trench MOSFET Oct 2009)

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an integrated SiC production system ass production o SIC SBDs 4

industry's first SiC power modules containing trench MOSFETs and SBDs that can be integrated into motors (Oct 2010)

Begin mass production of SiC MOSFETs (Dec 2010)

APEI Inc. (Arkansas Power Electronics International) and ROHM develop high-speed, high-current (1000A-class) SiC trench MOS modules

ROHM is expanding its lineup of SiC power devices with innovative new products that minimize power consumption in order to reduce greenhouse gas emissions and lessen

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